

L7 ANSWER 1 OF 51 CAPLUS COPYRIGHT 2003 ACS

AN 1999:184225 CAPLUS

DN 130:223059

TI Molecular compounds containing phenol derivatives as constituent

IN Aoki, Izuo; Sato, Takehiro; Amaike, Masato; Suzuki, Hiroshi

PA Nippon Soda Co., Ltd., Japan

SO PCT Int. Appl., 339 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9911609	A1	19990311	WO 1998-JP3917	19980902
	W: US				
	RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	JP 11189565	A2	19990713	JP 1998-276724	19980902
	EP 1016656	A1	20000705	EP 1998-941671	19980902
	R: DE, FR, GB, IT				
PRAI	JP 1997-252930	A	19970902		
	JP 1997-308058	A	19971022		
	WO 1998-JP3917	W	19980902		

OS MARPAT 130:223059

IT 221085-36-5P

RL: CAT (Catalyst use); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (epoxy resin hardener, inclusion compd.; mol. compds. (inclusion compds.) contg. phenol derivs. as hosts for imparting chem. or thermal stability and slow releasability, to org. compds.)

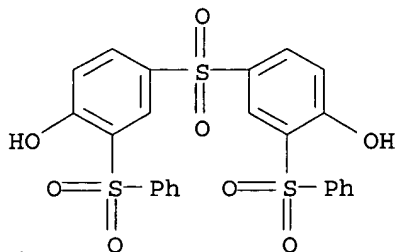
RN 221085-36-5 CAPLUS

CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)-, compd. with 2-ethyl-4-methyl-1H-imidazole (1:2) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

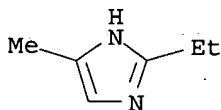
CMF C24 H18 O8 S3



CM 2

CRN 931-36-2

CMF C6 H10 N2



IT 221085-37-6P 221085-38-7P 221085-39-8P

221085-40-1P 221085-41-2P

RL: NUU (Other use, unclassified); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(inclusion compd.; mol. compds. (inclusion compds.) contg. phenol derivs. as hosts for imparting chem. or thermal stability and slow releasability, to org. compds.)

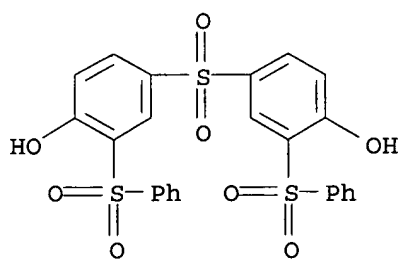
RN 221085-37-6 CAPLUS

CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)-, compd. with pyridine (1:2) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

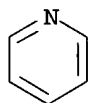
CMF C24 H18 O8 S3



CM 2

CRN 110-86-1

CMF C5 H5 N



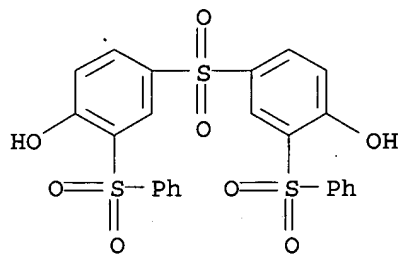
RN 221085-38-7 CAPLUS

CN 2-Imidazolidinone, 1,3-dimethyl-, compd. with pyridine and 4,4'-sulfonylbis[2-(phenylsulfonyl)phenol] (1:1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

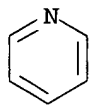
CMF C24 H18 O8 S3



CM 2

CRN 110-86-1

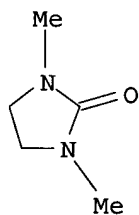
CMF C5 H5 N



CM 3

CRN 80-73-9

CMF C5 H10 N2 O



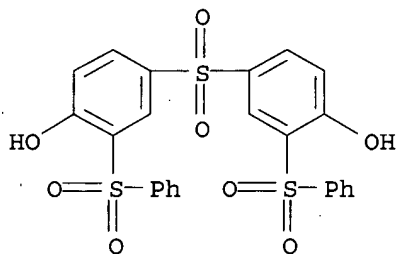
RN 221085-39-8 CAPLUS

CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)-, compd. with tetrahydrofuran  
(1:4) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

CMF C24 H18 O8 S3



CM 2

CRN 109-99-9

CMF C4 H8 O



RN 221085-40-1 CAPLUS

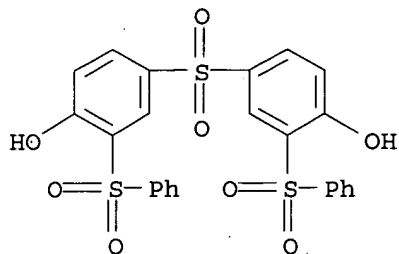
CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)-, compd. with 1,4-dioxane

(1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

CMF C24 H18 O8 S3



CM 2

CRN 123-91-1

CMF C4 H8 O2



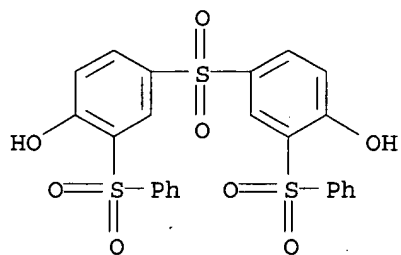
RN 221085-41-2 CAPLUS

CN Formamide, N,N-dimethyl-, compd. with 4,4'-sulfonylbis[2-(phenylsulfonyl)phenol] (3:2) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

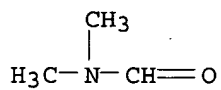
CMF C24 H18 O8 S3



CM 2

CRN 68-12-2

CMF C3 H7 N O



IT 221085-34-3P 221085-35-4P

RL: AGR (Agricultural use); BUU (Biological use, unclassified); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); BIOL (Biological study); PREP (Preparation); USES (Uses) (industrial disinfectant, inclusion compd.; mol. compds. (inclusion compds.) contg. phenol derivs. as hosts for imparting chem. or thermal stability and slow releasability, to org. compds.)

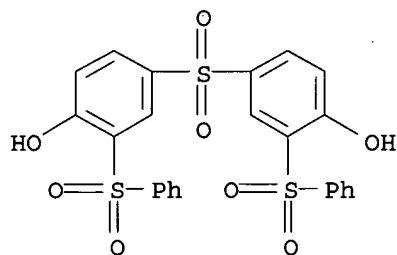
RN 221085-34-3 CAPLUS

CN 3(2H)-Isothiazolone, 5-chloro-2-methyl-, compd. with 4,4'-sulfonylbis[2-(phenylsulfonyl)phenol] (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

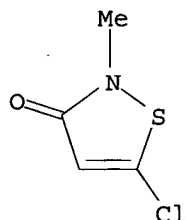
CMF C24 H18 O8 S3



CM 2

CRN 26172-55-4

CMF C4 H4 Cl N O S



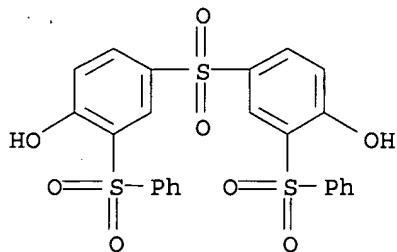
RN 221085-35-4 CAPLUS

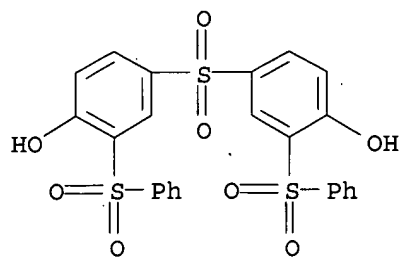
CN 3(2H)-Isothiazolone, 5-chloro-2-methyl-, compd. with 4,4'-sulfonylbis[2-(phenylsulfonyl)phenol] (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 177325-72-3

CMF C24 H18 O8 S3

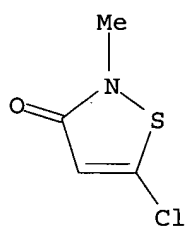




CM 2

CRN 26172-55-4

CMF C4 H4 Cl N O S



RE.CNT 12

THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L7 ANSWER 6 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1996:338221 CAPLUS  
 DN 125:22377  
 TI Sulfonyl compound and thermal-sensitive recording medium using the same  
 IN Saito, Toranosuke; Oda, Shigeru; Kawabata, Eiji  
 PA Sanko Kaihatsu Kagaku Kenkyusho, Japan  
 SO Eur. Pat. Appl., 34 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 706997	A1	19960417	EP 1995-116182	19951013
	EP 706997	B1	19980311		
	R: BE, DE, GB				
	JP 08269000	A2	19961015	JP 1995-247319	19950926
	JP 3273403	B2	20020408		
	US 5705452	A	19980106	US 1995-540722	19951011
PRAI	JP 1994-249265	A	19941014		
	JP 1995-12134	A	19950130		

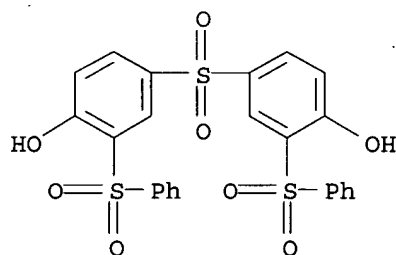
OS MARPAT 125:22377

IT 177325-72-3P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (prepd. as developer for thermal sensitive recording material)

RN 177325-72-3 CAPLUS

CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)- (9CI) (CA INDEX NAME)



L7 ANSWER 7 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1995:846608 CAPLUS  
 DN 124:246475  
 TI Positive working recording material with improved developability  
 IN Elsaesser, Andreas; Buhr, Gerhard  
 PA Hoechst A.-G., Germany  
 SO Ger. Offen., 10 pp.  
 CODEN: GWXXBX

DT Patent  
 LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4401940	A1	19950727	DE 1994-4401940	19940124
	EP 668540	A1	19950823	EP 1995-100490	19950116
	EP 668540	B1	20000510		
	R: DE, FR, GB, IT, NL				
	BR 9500283	A	19951017	BR 1995-283	19950123
	JP 07287392	A2	19951031	JP 1995-9246	19950124
	US 5753405	A	19980519	US 1996-674971	19960703
PRAI	DE 1994-4401940		19940124		

US 1995-374906 19950119

OS MARPAT 124:246475

IT 151438-20-9 151438-21-0

RL: MOA (Modifier or additive use); USES (Uses)  
(Pos. working recording material with improved developability)

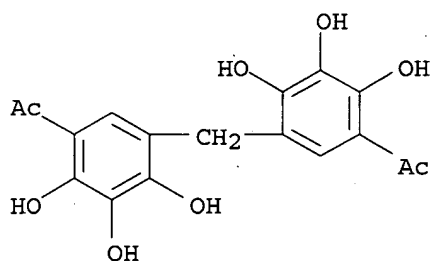
RN 151438-20-9 CAPLUS

CN 1-Naphthalenesulfonic acid, 3-diazo-3,4-dihydro-4-oxo-, ester with  
1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI)  
(CA INDEX NAME)

CM 1

CRN 168766-34-5

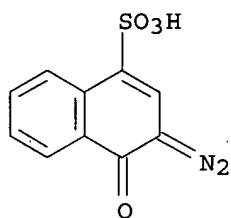
CMF C17 H16 O8



CM 2

CRN 20680-48-2

CMF C10 H6 N2 O4 S



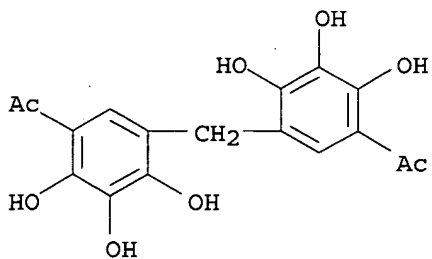
RN 151438-21-0 CAPLUS

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with  
1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI)  
(CA INDEX NAME)

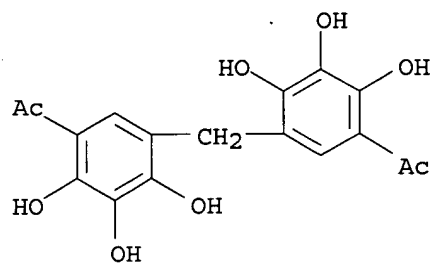
CM 1

CRN 168766-34-5

CMF C17 H16 O8



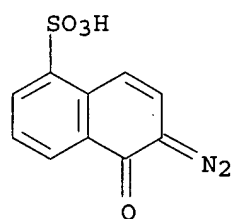




CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



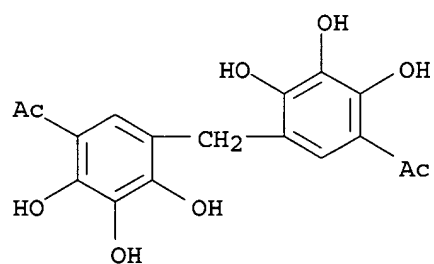
IT 168766-34-5 168766-38-9

RL: MOA (Modifier or additive use); USES (Uses)

(development promoter; Pos. working recording material with improved developability)

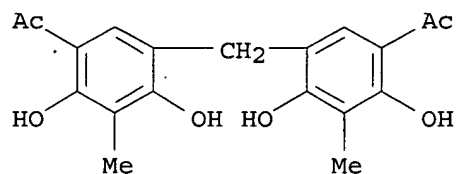
RN 168766-34-5 CAPLUS

CN Ethanone, 1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)  
(CA INDEX NAME)



RN 168766-38-9 CAPLUS

CN Ethanone, 1,1'-[methylenebis(4,6-dihydroxy-5-methyl-3,1-phenylene)]bis-  
(9CI) (CA INDEX NAME)



L7 ANSWER 10 OF 51 CAPLUS COPYRIGHT 2003 ACS

AN 1994:65973 CAPLUS

DN 120:65973

TI Thermosensitive recording material

IN Nishimura, Masaki; Toyofuku, Kunitaka

PA Oji Paper Co., Ltd., Japan

SO Eur. Pat. Appl., 16 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 535788	A1	19930407	EP 1992-307170	19920805
	EP 535788	B1	19970305		
	R: DE, GB				
	JP 05085059	A2	19930406	JP 1991-251364	19910930
	US 5384303	A	19950124	US 1992-916693	19920722
PRAI	JP 1991-251364		19910930		

OS MARPAT 120:65973

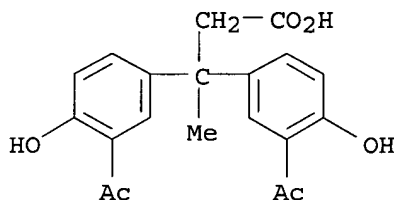
IT 151533-18-5

RL: USES (Uses)

(color-forming compns. contg. dye precursors and, for thermosensitive recording materials)

RN 151533-18-5 CAPLUS

CN Benzenepropanoic acid, 3-acetyl-.beta.-(3-acetyl-4-hydroxyphenyl)-4-hydroxy-.beta.-methyl- (9CI) (CA INDEX NAME)



L7 ANSWER 11 OF 51 CAPLUS COPYRIGHT 2003 ACS

AN 1993:588611 CAPLUS

DN 119:188611

TI Thrombolysis-accelerating agents containing diphenylhydrocarbons

IN Kaiho, Tatsuo; Matsunaga, Akio; Myamoto, Michihiko; Okumura, Kunio;

Tanada, Hideki; Kosaka, Katsuhiko; Tamatsukuri, Atsushi

PA Mitsui Toatsu Chemicals, Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05170687	A2	19930709	JP 1991-338382	19911220
PRAI	JP 1991-338382		19911220		

OS MARPAT 119:188611

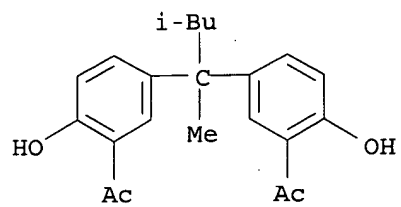
IT 150371-94-1P

RL: PREP (Preparation)

(prepn. and .alpha.2-plasmin inhibitor inhibitory activity of, as thrombolytic)

RN 150371-94-1 CAPLUS

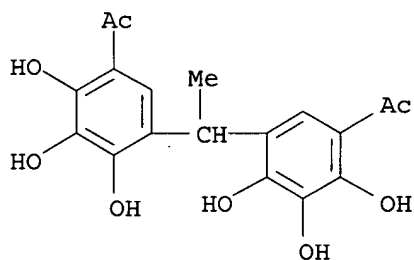
CN Ethanone, 1,1'-[(1,3-dimethylbutylidene)bis(6-hydroxy-3,1-phenylene)]bis- (9CI) (CA INDEX NAME)



=>

L7 ANSWER 12 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1993:202100 CAPLUS  
 DN 118:202100  
 TI Positive-working photoresist compositions providing high resolution pattern  
 IN Kawabe, Yasumasa; Sakaguchi, Shinji; Kokubo, Tadayoshi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 19 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04296755	A2	19921021	JP 1991-62152	19910326
PRAI	JP 1991-62152		19910326		
OS	MARPAT 118:202100				
IT	<b>128197-51-3, 1,1'-(5,5'-Diacetyl-2,3,4,2',3',4'-hexahydroxy</b> <b>)diphenylethane</b> RL: USES (Uses) (photoresist contg. quinonediazide compd. and)				
RN	128197-51-3 CAPLUS				
CN	Ethanone, 1,1'-[ethylidenebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI) (CA INDEX NAME)				



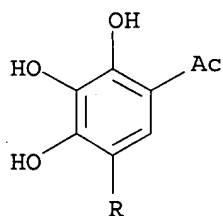
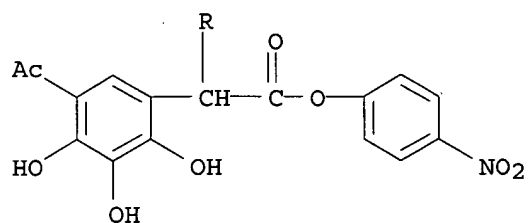
L7 ANSWER 13 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1993:136265 CAPLUS  
 DN 118:136265  
 TI Photosensitive lithographic printing plate  
 IN Nagashima, Akira; Uenishi, Kazuya  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 12 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03239261	A2	19911024	JP 1990-35665	19900216
PRAI	JP 1990-35665		19900216		
IT	<b>128152-12-5 128197-51-3, 1,1'-(5,5'-Diacetyl-</b> <b>2,3,4,2',3',4'-hexahydroxy)diphenylethane 128347-37-5</b> <b>143868-77-3</b> RL: RCT (Reactant); RACT (Reactant or reagent) (esterification of, in prepn. of photosensitizers for lithog. printing plates)				
RN	128152-12-5 CAPLUS				
CN	Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)- 2,3,4-trihydroxy-, 4-nitrophenyl ester, 6-diazo-5,6-dihydro-5-oxo-1- naphthalenesulfonate (9CI) (CA INDEX NAME)				

CM 1

CRN 128347-40-0

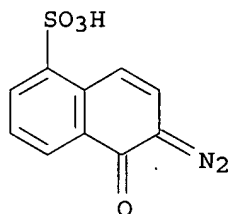
CMF C24 H19 N O12



CM 2

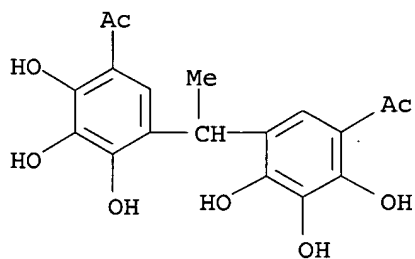
CRN 20546-03-6

CMF C10 H6 N2 O4 S



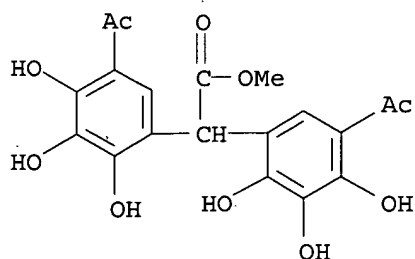
RN 128197-51-3 CAPLUS

CN Ethanone, 1,1'-[ethyldienebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)  
(CA INDEX NAME)

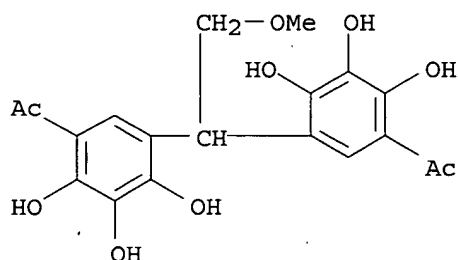


RN 128347-37-5 CAPLUS

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-  
2,3,4-trihydroxy-, methyl ester (9CI) (CA INDEX NAME)



RN 143868-77-3 CAPLUS  
 CN Ethanone, 1,1'-[(2-methoxyethylidene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI) (CA INDEX NAME)



L7 ANSWER 14 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1993:113172 CAPLUS  
 DN 118:113172  
 TI Photosensitive lithographic printing plate  
 IN Nagashima, Akira; Uenishi, Kazuya  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 18 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03239262	A2	19911024	JP 1990-35666	19900216
PRAI	JP 1990-35666		19900216		

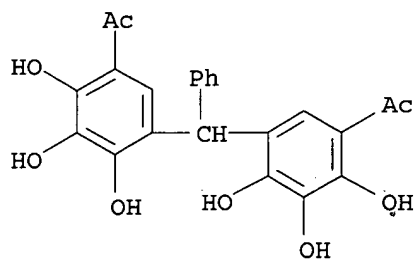
IT 133682-16-3D, phenol derivs.

RL: USES (Uses)

(esterification reaction of, in prepn. of photosensitizers for lithog. printing plates)

RN 133682-16-3 CAPLUS

CN Ethanone, 1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI) (CA INDEX NAME)



L7 ANSWER 15 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1992:140130 CAPLUS  
 DN 116:140130  
 TI Positive-type photoresist composition  
 IN Kawabe, Yasumasa; Uenishi, Kazuya; Tan, Shiro  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 34 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 445819	A2	19910911	EP 1991-103511	19910307
	EP 445819	A3	19911211		
	EP 445819	B1	20010822		
	R: DE, GB				
	JP 03259149	A2	19911119	JP 1990-57658	19900308
	JP 03279958	A2	19911211	JP 1990-80028	19900328
	JP 03279959	A2	19911211	JP 1990-80029	19900328
PRAI	JP 1990-57658	A	19900308		
	JP 1990-80028	A	19900328		
	JP 1990-80029	A	19900328		

OS MARPAT 116:140130

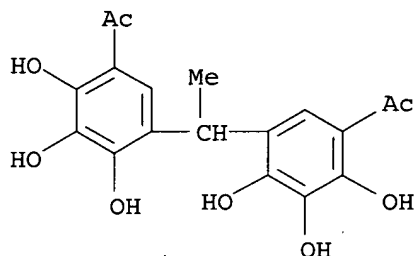
IT 128197-51-3, 1,1'-(5,5'-Diacetyl-2,3,4,2',3',4'-hexahydroxy  
 )diphenylethane

RL: USES (Uses)

(pos. photoresist compns. contg.)

RN 128197-51-3 CAPLUS

CN Ethanone, 1,1'-[ethylidenebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)  
 (CA INDEX NAME)



L7 ANSWER 16 OF 51 CAPLUS COPYRIGHT 2003 ACS

AN 1991:666881 CAPLUS

DN 115:266881

TI Positive-working photoresist composition containing acetal solvent

IN Kawabe, Yasumasa; Kokubo, Tadayoshi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03056960	A2	19910312	JP 1989-192888	19890726
PRAI	JP 1989-192888		19890726		

IT 135977-06-9

RL: USES (Uses)

(photoresist compn. contg. acetal solvent and, for soln. stability)

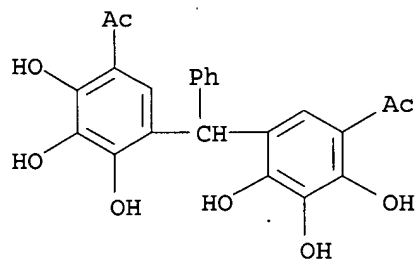
RN 135977-06-9 CAPLUS

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with  
1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone]  
(9CI) (CA INDEX NAME)

CM 1

CRN 133682-16-3

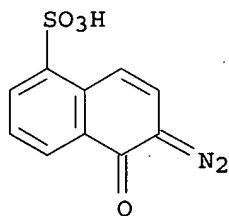
CMF C23 H20 O8



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



=>



L7 ANSWER 17 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1991:523862 CAPLUS  
 DN 115:123862  
 TI Positive-working photoresist composition  
 IN Kawabe, Yasumasa; Kokubo, Tadayoshi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

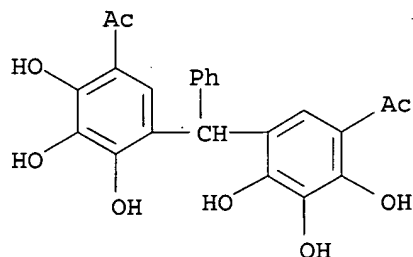
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 02247653	A2	19901003	JP 1989-68751	19890320
	JP 2584311	B2	19970226		
PRAI	JP 1989-68751		19890320		
IT	135977-06-9				

RL: USES (Uses)  
 (photosensitizer, photoresist compn. contg.)

RN 135977-06-9 CAPLUS  
 CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with  
 1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone]  
 (9CI) (CA INDEX NAME)

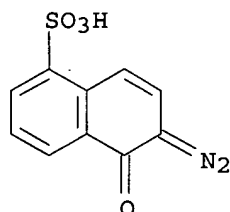
CM 1

CRN 133682-16-3  
 CMF C23 H20 O8



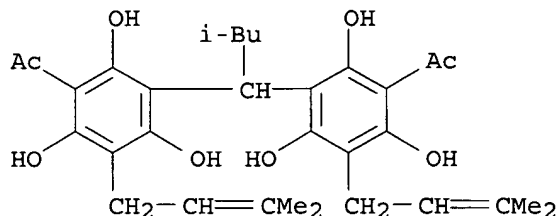
CM 2

CRN 20546-03-6  
 CMF C10 H6 N2 O4 S



L7 ANSWER 18 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1991:489122 CAPLUS  
 DN 115:89122  
 TI Demethylacrovostone from Achronychia pedunculata fruits  
 AU De Silva, Leslie B.; Herath, Wimal M.; Lyanage, Chandani; Kumar, Vijaya;

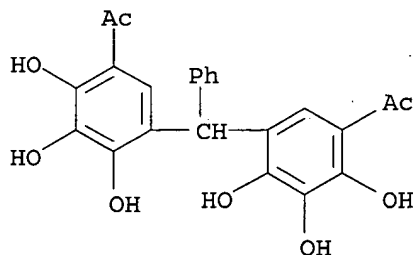
Ahmad, Viqar Uddin; Sultana, Azra  
 CS Nat. Prod. Chem. Div., Med. Res. Inst., Colombo, Sri Lanka  
 SO Phytochemistry (1991), 30(5), 1709-10  
 CODEN: PYTCAS; ISSN: 0031-9422  
 DT Journal  
 LA English  
 IT **135383-99-2**, Demethylacrovestone  
 RL: BIOL (Biological study)  
 (from *Acronychia pedunculata* fruits)  
 RN 135383-99-2 CAPLUS  
 CN Ethanone, 1,1'-[(3-methylbutylidene)bis[2,4,6-trihydroxy-5-(3-methyl-2-butenyl)-3,1-phenylene]]bis- (9CI) (CA INDEX NAME)



L7 ANSWER 19 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1991:256969 CAPLUS  
 DN 114:256969  
 TI Positive-working photoresist composition  
 IN Uenishi, Kazuya; Sakaguchi, Shinji; Kokubo, Tadayoshi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Eur. Pat. Appl., 29 pp.  
 CODEN: EPXXDW  
 DT Patent  
 LA English  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 395049	A1	19901031	EP 1990-107925	19900426
	EP 395049	B1	19990721		
	R: BE, DE, FR, GB				
	JP 02285351	A2	19901122	JP 1989-107013	19890426
	JP 2700918	B2	19980121		
	US 5173389	A	19921222	US 1990-514811	19900426
PRAI	JP 1989-107013		19890426		

IT **133682-16-3D**, dimethylhydroxybenzyl deriv.,  
 diazidonaphthoquinone sulfate  
 RL: USES (Uses)  
 (pos. photoresists contg. alkali-sol. novolak resins and)  
 RN 133682-16-3 CAPLUS  
 CN Ethanone, 1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI) (CA INDEX NAME)



L7 ANSWER 24 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1990:468417 CAPLUS  
 DN 113:68417  
 TI Positive-working photoresist composition  
 IN Uenishi, Kazuya; Kawabe, Yasumasa; Kokubo, Tadayoshi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 01309052	A2	19891213	JP 1988-139904	19880607
	JP 2552900	B2	19961113		
	US 5089373	A	19920218	US 1989-363568	19890607
PRAI	JP 1988-139904		19880607		

IT 128152-08-9 128152-12-5 128197-52-4

RL: USES (Uses)  
 (pos.-working photoresist compn. contg.)

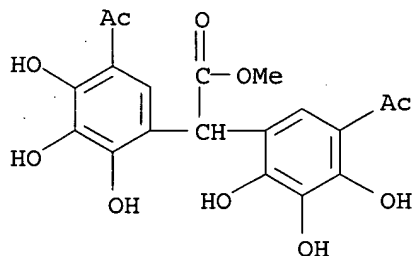
RN 128152-08-9 CAPLUS

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-  
 2,3,4-trihydroxy-, methyl ester, 6-diazo-5,6-dihydro-5-oxo-1-  
 naphthalenesulfonate (9CI) (CA INDEX NAME)

CM 1

CRN 128347-37-5

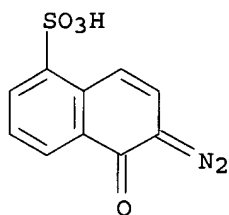
CMF C19 H18 O10



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



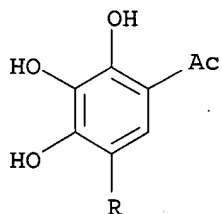
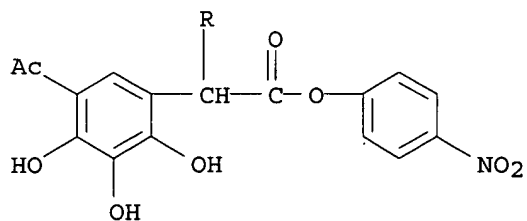
RN 128152-12-5 CAPLUS

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-  
 2,3,4-trihydroxy-, 4-nitrophenyl ester, 6-diazo-5,6-dihydro-5-oxo-1-  
 naphthalenesulfonate (9CI) (CA INDEX NAME)

CM 1

CRN 128347-40-0

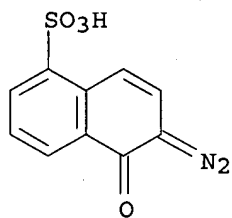
CMF C24 H19 N O12



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



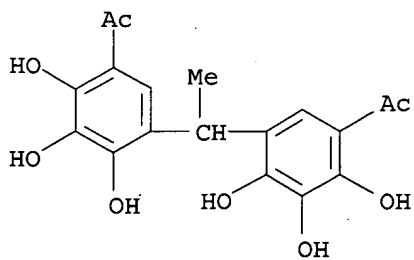
RN 128197-52-4 CAPLUS

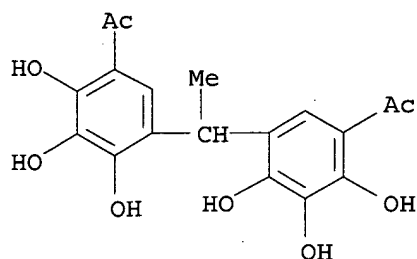
CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, tetraester with 1,1'-[ethylidenebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI) (CA INDEX NAME)

CM 1

CRN 128197-51-3

CMF C18 H18 O8

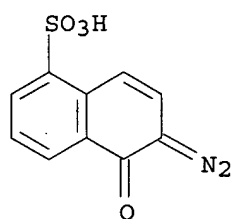




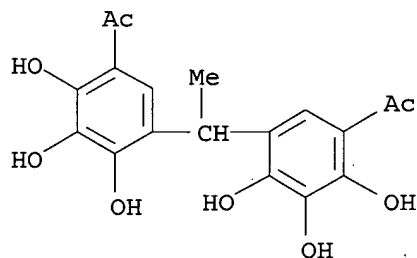
CM 2

CRN 20546-03-6

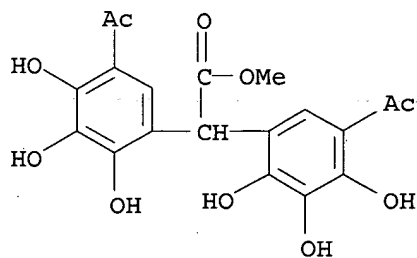
CMF C10 H6 N2 O4 S

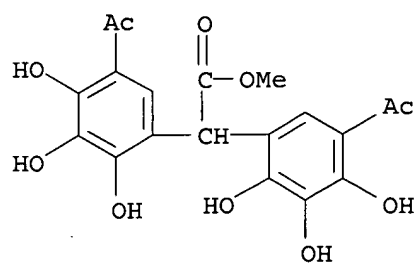


IT 128197-51-3, 1,1-(5,5'-Diacetyl-2,3,4,2',3',4'-**hexahydroxy**  
 )diphenylethane 128347-37-5, 1,1-(5,3'-Diacetyl-2,3,4,4',5',6'-  
**hexahydroxy**)diphenylacetic acid methyl ester 128347-40-0  
 RL: RCT (Reactant); RACT (Reactant or reagent)  
 (reaction of, in prepn. of naphthoquinonediazide ester for pos.-working  
 photoresist compn.)  
 RN 128197-51-3 CAPLUS  
 CN Ethanone, 1,1'-[ethylidenebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)  
 (CA INDEX NAME)



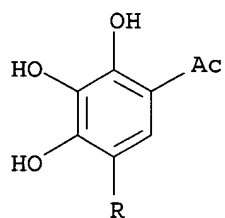
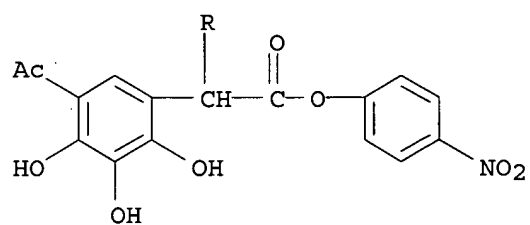
RN 128347-37-5 CAPLUS  
 CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-  
 2,3,4-trihydroxy-, methyl ester (9CI) (CA INDEX NAME)





RN 128347-40-0 CAPLUS

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-2,3,4-trihydroxy-, 4-nitrophenyl ester (9CI) (CA INDEX NAME)



L7 ANSWER 35 OF 51 CAPLUS COPYRIGHT 2003 ACS

AN 1964:483903 CAPLUS

DN 61:83903

OREF 61:14569h,14570a-d

TI Preparation of phenolic polynuclear compounds with sulfonyl bridges

AU Kaemmerer, H.; Harris, M.

CS Univ. Mainz/Rhein, Germany

SO J. Polymer. Sci. (1964), 2(Pt. A;9), 4003-10

DT Journal

LA Unavailable

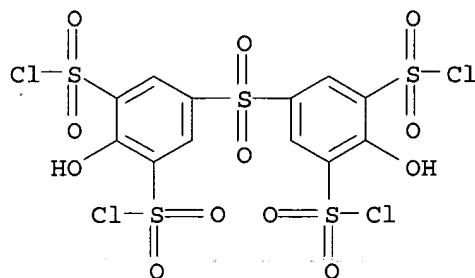
GI For diagram(s), see printed CA Issue.

AB By use of the Fries rearrangement, 8 new sulfones were prepd. 6,6'-**Dihydroxy**-3,3'-dimethyldiphenyl sulfone (6 millimoles) was dissolved in 15 ml. ClSO<sub>3</sub>H, and the mixt. heated for 1 hr. at 40-50.degree.. After 24 hrs. at room temp., the mixt. was added to ice to ppt. I (R<sub>2</sub> = R<sub>4</sub> = H, R<sub>3</sub> = Me, R = OH, R<sub>1</sub> = R<sub>5</sub> = ClSO<sub>2</sub>) (Ia), m. 184-7.degree. (petr. ether). 4,4'-**Dihydroxydiphenyl** sulfone (II) (0.01 mole) added to 40 ml. ClSO<sub>3</sub>H and the mixt. treated similarly, gave III (R = H), m. 201-3.degree. (dioxane). II (12 millimoles) added to 50 ml. ClSO<sub>3</sub>H and the mixt. heated for 3-4 hrs. at 130-140.degree. and kept overnight gave III (R = ClO<sub>2</sub>S), m. 230-40.degree. (decompn.) (dioxane). MeC<sub>6</sub>H<sub>4</sub>SO<sub>2</sub>Cl (19 g.) was added to 45 ml. Me<sub>2</sub>CO and 16.5 g. Na salt of 3,4-Cl(HO)C<sub>6</sub>H<sub>3</sub>Me and the mixt. shaken and poured into H<sub>2</sub>O; 5 g. of the resulting 4,2-MeClC<sub>6</sub>H<sub>3</sub>O<sub>3</sub>SC<sub>6</sub>H<sub>4</sub>Me-4 was treated with AlCl<sub>3</sub> at 110.degree. and 150.degree., and the mixt. decompd. with HCl-ice and stirred. The resulting solid was dissolved in 10% KOH and acidified to give I (R = R<sub>1</sub> = R<sub>3</sub> = R<sub>4</sub> = H, R<sub>2</sub> = Me, R<sub>5</sub> = Cl), m. 146-7.5.degree. (alc.) I (R = R<sub>1</sub> = R<sub>3</sub> = R<sub>4</sub> = Me, R<sub>2</sub> = Br, R<sub>5</sub> = Cl), m. 152-3.degree. (alc.), was prepd. from 6 g. 4-bromo-2,3,5,6-tetramethylbenzenesulfonyl chloride, 40 ml. Me<sub>2</sub>CO, and 3.3 g. Na salt of 3-chloro-4-**hydroxytoluene** Na salt of 3',4-dimethyl-6'**hydroxydiphenyl** sulfone, 10 ml. H<sub>2</sub>O, and 1.9 g. p-MeC<sub>6</sub>H<sub>4</sub>SO<sub>2</sub>Cl gave, in a similar manner, 4,2,6-Me(p-MeC<sub>6</sub>H<sub>4</sub>SO<sub>2</sub>)<sub>2</sub>-C<sub>6</sub>H<sub>2</sub>OH, m. 221-3.degree. (CHCl<sub>3</sub>-petr. ether). IV was prepd. by heating a mixt. of 3.1 g. 4-**hydroxy**-3,5-toluenedisulfonyl chloride, 15 ml. 3-chloro-4-methoxytoluene (V), and 6 ml. SnCl<sub>4</sub> for 70 hrs. at 90.degree.. The mixt. was poured into H<sub>2</sub>O and the brown org. layer collected and steam-distd. The residue was boiled with MeOH, and the product demethylated with HI to give IV, m. 238-40.degree. (C<sub>6</sub>H<sub>6</sub>). VI, prepd. similarly from 15 ml. V, 4.75 g. Ia, and 6 ml. SnCl<sub>4</sub>, m. 246-52.degree. (AcOH-H<sub>2</sub>O).

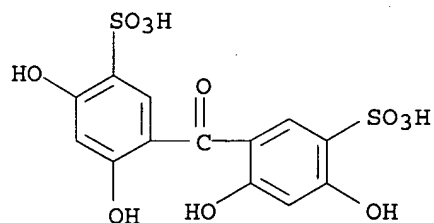
IT 92317-01-6, m-Benzenedisulfonyl chloride, 5,5'-sulfonylbis[2-**hydroxy**- (prepn. of)

RN 92317-01-6 CAPLUS

CN m-Benzenedisulfonyl chloride, 5,5'-sulfonylbis[2-hydroxy- (7CI) (CA INDEX NAME)



L7 ANSWER 41 OF 51 USPATFULL  
 AN 2002:230490 USPATFULL  
 TI Inhibition of pulp and paper yellowing using nitroxides,  
 hydroxylamines and other coadditives  
 IN Seltzer, Raymond R., New City, NY, United States  
 Wolf, Jean-Pierre, Courtaman, SWITZERLAND  
 Heitner, Cyril, Pierrefonds, CANADA  
 Schmidt, John A., L'ile Bizard, CANADA  
 McGarry, Peter F., L'ile Bizard, CANADA  
 Cunkle, Glen T., Stamford, CT, United States  
 Nelson, Randall B., Seattle, WA, United States  
 PA Ciba Specialty Chemicals Corporation, Tarrytown, NY, United States (U.S.  
 corporation)  
 PI US 6447644 B1 20020910  
 US 2002124980 A1 20020912  
 AI US 2001-974382 20011010 (9)  
 RLI Division of Ser. No. US 2000-573401, filed on 18 May 2000 Division of  
 Ser. No. US 1998-119567, filed on 20 Jul 1998, now patented, Pat. No. US  
 6254724, issued on 3 Jul 2001  
 PRAI US 1997-54968P 19970807 (60)  
 US 1997-53489P 19970723 (60)  
 DT Utility  
 FS GRANTED  
 EXNAM Primary Examiner: Griffin, Steven P.; Assistant Examiner: Halpern, Mark  
 LREP Stevenson, Tyler A., Hall, Luther A. R.  
 CLMN Number of Claims: 34  
 ECL Exemplary Claim: 1  
 DRWN 0 Drawing Figure(s); 0 Drawing Page(s)  
 LN.CNT 3054  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 184840-94-6  
 (inhibition of pulp and paper yellowing using nitroxides and other  
 co-additives)  
 RN 184840-94-6 USPATFULL  
 CN Benzenesulfonic acid, 3,3'-carbonylbis[4,6-dihydroxy-, disodium salt (9CI)  
 (CA INDEX NAME)



● 2 Na

L7 ANSWER 42 OF 51 USPATFULL  
 AN 1998:54656 USPATFULL  
 TI Positive-working recording material containing aluminum base and  
 mat-finished quinone diazide layer developable in weak alkaline  
 developers  
 IN Elsaesser, Andreas, Idstein, Germany, Federal Republic of  
 Buhr, Gerhard, Koenigstein, Germany, Federal Republic of  
 PA AGFA-Gevaert AG, Leverkusen, Germany, Federal Republic of (non-U.S.  
 corporation)  
 PI US 5753405 19980519  
 AI US 1996-674971 19960703 (8)



RLI Continuation of Ser. No. US 1995-374906, filed on 19 Jan 1995, now abandoned

PRAI DE 1994-4401940 19940124

DT Utility

FS Granted

EXNAM Primary Examiner: Young, Christopher G.

LREP Foley & Lardner

CLMN Number of Claims: 20

ECL Exemplary Claim: 1

DRWN No Drawings

LN.CNT 717

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 151438-20-9 151438-21-0

(Pos. working recording material with improved developability)

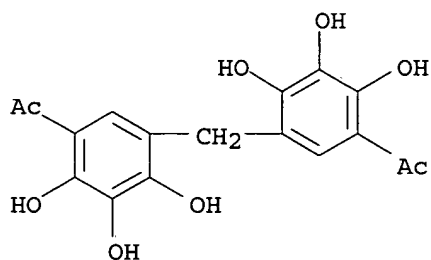
RN 151438-20-9 USPATFULL

CN 1-Naphthalenesulfonic acid, 3-diazo-3,4-dihydro-4-oxo-, ester with  
1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI)  
(CA INDEX NAME)

CM 1

CRN 168766-34-5

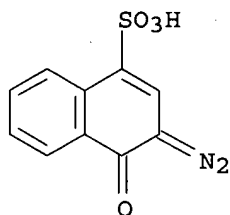
CMF C17 H16 O8



CM 2

CRN 20680-48-2

CMF C10 H6 N2 O4 S



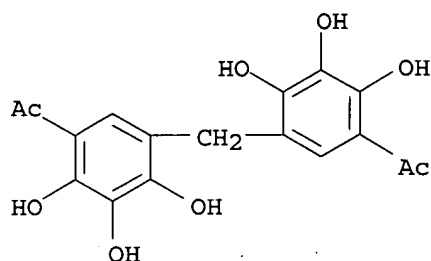
RN 151438-21-0 USPATFULL

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with  
1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI)  
(CA INDEX NAME)

CM 1

CRN 168766-34-5

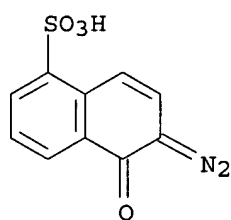
CMF C17 H16 O8



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S

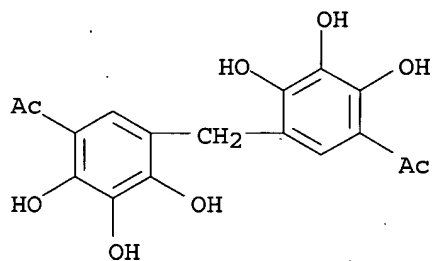


IT 168766-34-5 168766-38-9

(development promoter; Pos. working recording material with improved developability)

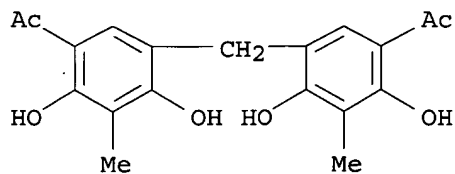
RN 168766-34-5 USPATFULL

CN Ethanone, 1,1'-[methylenebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)  
(CA INDEX NAME)



RN 168766-38-9 USPATFULL

CN Ethanone, 1,1'-[methylenebis(4,6-dihydroxy-5-methyl-3,1-phenylene)]bis-  
(9CI) (CA INDEX NAME)

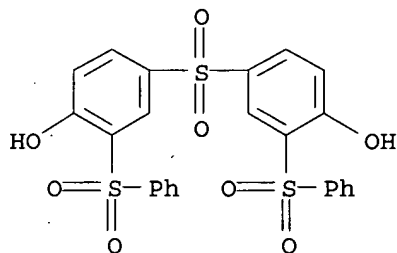


L7 ANSWER 43 OF 51 USPATFULL

AN 1998:1737 USPATFULL

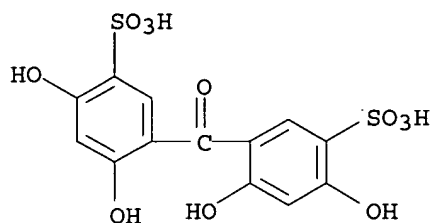
TI Sulfonyl compound and thermal-sensitive recording medium using the same

IN Saito, Toranosuke, Ibaraki, Japan  
 Oda, Shigeru, Ibaraki, Japan  
 Kawabata, Eiji, Ibaraki, Japan  
 PA Sanko Haihatsu Kagaku Kenkyusho, Ibaraki, Japan (non-U.S. corporation)  
 PI US 5705452 19980106  
 AI US 1995-540722 19951011 (8)  
 PRAI JP 1994-249265 19941014  
 JP 1995-12134 19950130  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Hess, Bruce H.  
 LREP Kane, Dalsimer, Sullivan, Kurucz, Levy, Eisele and Richard, LLP  
 CLMN Number of Claims: 2  
 ECL Exemplary Claim: 1  
 DRWN 16 Drawing Figure(s); 16 Drawing Page(s)  
 LN.CNT 715  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 177325-72-3P  
 (prepd. as developer for thermal sensitive recording material)  
 RN 177325-72-3 USPATFULL  
 CN Phenol, 4,4'-sulfonylbis[2-(phenylsulfonyl)- (9CI) (CA' INDEX NAME)



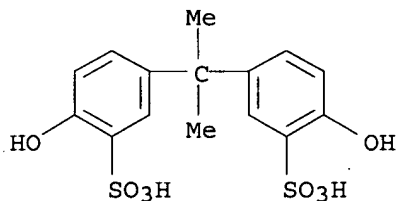
L7 ANSWER 5 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1997:9405 CAPLUS  
 DN 126:39783  
 TI Thermal recording material with improved light resistance  
 IN Ogino, Naomi; Oomori, Takashi; Ueda, Hiroshi; Midorikawa, Yoshimi; Wakita, Yutaka  
 PA Nippon Seishi Kk, Japan  
 SO Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08267922	A2	19961015	JP 1995-75866	19950331
	JP 2936556	B2	19990823		
PRAI	JP 1995-75866		19950331		
IT	<b>184840-94-6</b>				
	RL: DEV (Device component use); MOA (Modifier or additive use); USES (Uses)				
	(UV absorber; light-resistant thermal recording material contg. UV absorber and fluorescent dye)				
RN	184840-94-6	CAPLUS			
CN	Benzenesulfonic acid, 3,3'-carbonylbis[4,6-dihydroxy-, disodium salt (9CI)				
	(CA INDEX NAME)				



L7 ANSWER 9 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1995:226867 CAPLUS  
 DN 122:12274  
 TI Jet-printing inks, their stabilization and phenolsulfonic acids therefor  
 IN Van Toan Vien; Laver, Hugh Stephen; Leppard, David George  
 PA Ciba-Geigy A.-G., Switz.  
 SO Ger. Offen., 17 pp.  
 CODEN: GWXXBX  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4337862	A1	19940511	DE 1993-4337862	19931105
	US 5509957	A	19960423	US 1993-147706	19931104
	JP 06234945	A2	19940823	JP 1993-303400	19931109
PRAI	CH 1992-3456		19921109		
OS	MARPAT 122:12274				
IT	159411-67-3				
	RL: MOA (Modifier or additive use); USES (Uses)				
	(jet-printing inks, their stabilization and phenolsulfonic acids therefor)				
RN	159411-67-3	CAPLUS			
CN	Benzenesulfonic acid, 3,3'-(1-methylethylidene)bis[6-hydroxy-, dilithium salt (9CI) (CA INDEX NAME)				



L7 ANSWER 27 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1989:554634 CAPLUS  
 DN 111:154634  
 TI Heat-resistant aromatic polyester liquid crystals  
 IN Matsumoto, Tetsuo; Imamura, Takayuki; Tsujimoto, Keizo  
 PA Japan Ester Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 6 pp.  
 CODEN: JKXXAF

DT Patent  
 LA Japanese

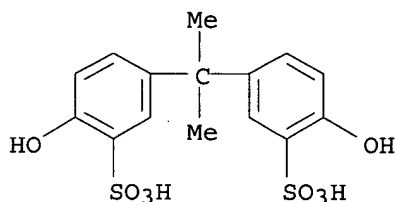
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 01060627	A2	19890307	JP 1987-214634	19870828
PRAI	JP 1987-214634		19870828		
IT	<b>123046-20-8P 123046-21-9P 123046-24-2P</b>				
	RL: PREP (Preparation)				
	(liq. crystal, prepn. of, heat-resistant with good melt moldability)				
RN	123046-20-8	CAPLUS			
CN	1,4-Benzenedicarboxylic acid, polymer with 4-hydroxybenzoic acid and 3,3'-(1-methylethylidene)bis[6-hydroxybenzenesulfonic acid] disodium salt (9CI) (CA INDEX NAME)				

CM 1

CRN 59970-82-0

CMF C15 H16 O8 S2 . 2 Na

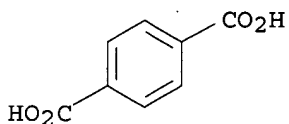


● 2 Na

CM 2

CRN 100-21-0

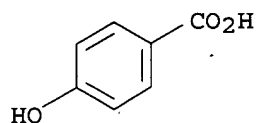
CMF C8 H6 O4



CM 3

CRN 99-96-7

CMF C7 H6 O3

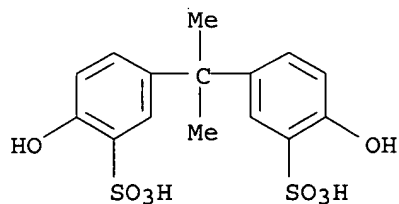


RN 123046-21-9 CAPLUS  
 CN 1,3-Benzenedicarboxylic acid, polymer with 1,4-benzenedicarboxylic acid, 4-hydroxybenzoic acid and 3,3'-(1-methylethylidene)bis[6-hydroxybenzenesulfonic acid] disodium salt (9CI) (CA INDEX NAME)

CM 1

CRN 59970-82-0

CMF C15 H16 O8 S2 . 2 Na

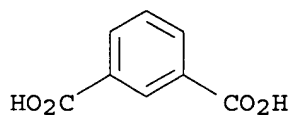


● 2 Na

CM 2

CRN 121-91-5

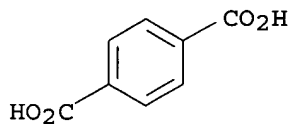
CMF C8 H6 O4



CM 3

CRN 100-21-0

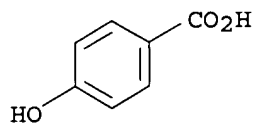
CMF C8 H6 O4



CM 4

CRN 99-96-7

CMF C7 H6 O3



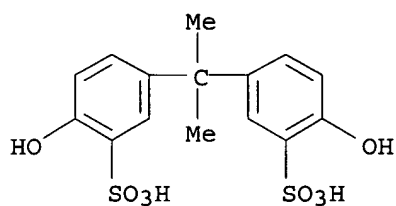
RN 123046-24-2 CAPLUS

CN 1,4-Benzenedicarboxylic acid, polymer with 6-hydroxy-2-naphthalenecarboxylic acid and 3,3'-(1-methylethylidene)bis[6-hydroxybenzenesulfonic acid] disodium salt (9CI) (CA INDEX NAME)

CM 1

CRN 59970-82-0

CMF C15 H16 O8 S2 . 2 Na

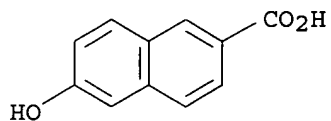


● 2 Na

CM 2

CRN 16712-64-4

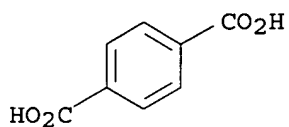
CMF C11 H8 O3



CM 3

CRN 100-21-0

CMF C8 H6 O4





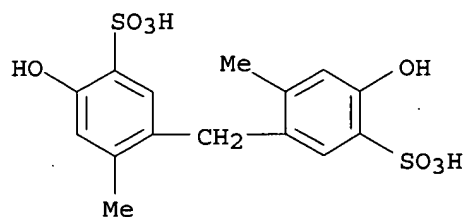
L7 ANSWER 33 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1981:532502 CAPLUS  
 DN 95:132502  
 TI Biphenylmethane derivative and pharmaceutical compositions containing it  
 IN Klemm, Kurt; Haerlin, Ruediger; Zick, Franz; Baron, Lothar; Pruesse, Wolfgang; Krueger, Uwe  
 PA Byk-Gulden Lomberg Chemische Fabrik G.m.b.H., Fed. Rep. Ger.  
 SO Eur. Pat. Appl., 34 pp.  
 CODEN: EPXXDW  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 29990	A1	19810610	EP 1980-107328	19801125
	EP 29990	B1	19820908		
	R: AT, BE, CH, DE, FR, GB, IT, LU, NL, SE				
	AT 1523	E	19820915	AT 1980-107328	19801125
	IL 61600	A1	19840629	IL 1980-61600	19801201
	AU 8064997	A1	19810611	AU 1980-64997	19801202
	AU 535714	B2	19840405		
	DK 8005175	A	19810605	DK 1980-5175	19801203
	ZA 8007544	A	19811125	ZA 1980-7544	19801203
	ES 497410	A1	19820101	ES 1980-497410	19801203
	JP 56113754	A2	19810907	JP 1980-171453	19801204
PRAI	CH 1979-10763		19791204		
	EP 1980-107328		19801125		
IT	79093-73-5P 79093-74-6P 79093-75-7P 79093-76-8P 79093-77-9P 79093-78-0P 79093-79-1P 79093-80-4P 79093-81-5P 79105-65-0P 79105-66-1P RL: SPN (Synthetic preparation); PREP (Preparation) (prepn. of)				
RN	79093-73-5 CAPLUS				
CN	Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with 1,4-dimethylpiperazine (1:1) (9CI) (CA INDEX NAME)				

CM 1

CRN 78480-14-5

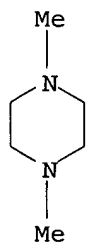
CMF C15 H16 O8 S2



CM 2

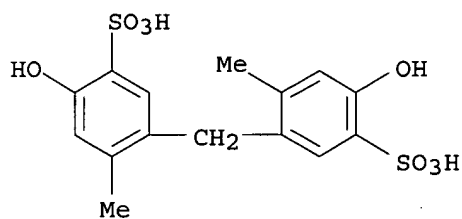
CRN 106-58-1

CMF C6 H14 N2



RN 79093-74-6 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, disodium salt (9CI) (CA INDEX NAME)



●2 Na

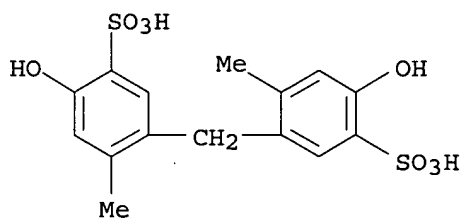
RN 79093-75-7 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with 1,2-ethanediamine (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

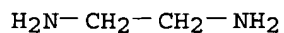
CMF C15 H16 O8 S2



CM 2

CRN 107-15-3

CMF C2 H8 N2



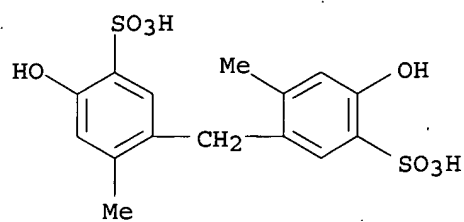
RN 79093-76-8 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with 1-methylpiperazine (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

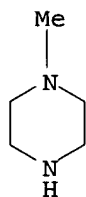
CMF C15 H16 O8 S2



CM 2

CRN 109-01-3

CMF C5 H12 N2



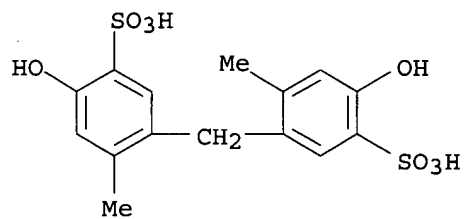
RN 79093-77-9 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with 1,4-bis(phenylmethyl)piperazine (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

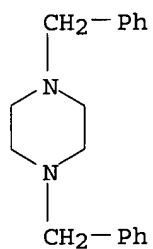
CMF C15 H16 O8 S2



CM 2

CRN 1034-11-3

CMF C18 H22 N2

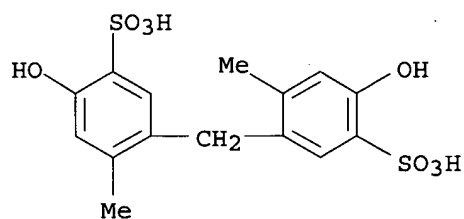


RN 79093-78-0 CAPLUS  
 CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with  
 1-methyl-4-(phenylmethyl)piperazine (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

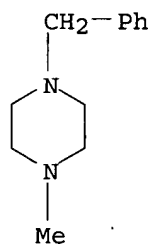
CMF C15 H16 O8 S2



CM 2

CRN 62226-74-8

CMF C12 H18 N2

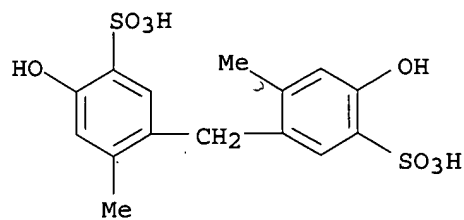


RN 79093-79-1 CAPLUS  
 CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with  
 morpholine (1:2) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

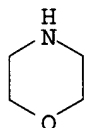
CMF C15 H16 O8 S2



CM 2

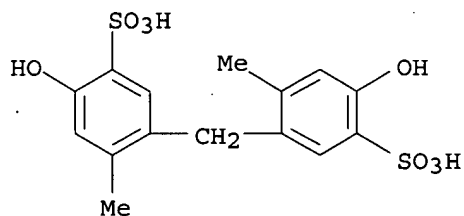
CRN 110-91-8

CMF C4 H9 N O



RN 79093-80-4 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, barium salt (1:1) (9CI) (CA INDEX NAME)



● Ba

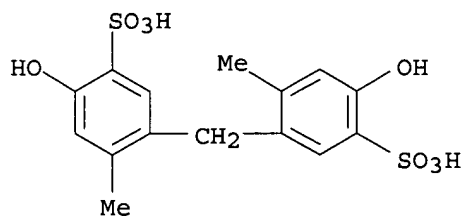
RN 79093-81-5 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with hydrazine (1:2) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

CMF C15 H16 O8 S2



CM 2

CRN 302-01-2

CMF H4 N2

H<sub>2</sub>N-NH<sub>2</sub>

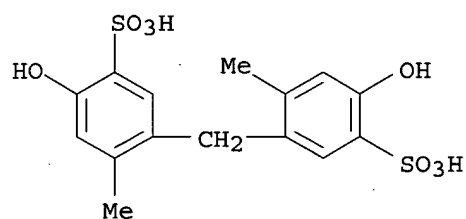
RN 79105-65-0 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with piperazine (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

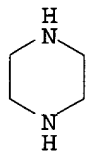
CMF C15 H16 O8 S2



CM 2

CRN 110-85-0

CMF C4 H10 N2



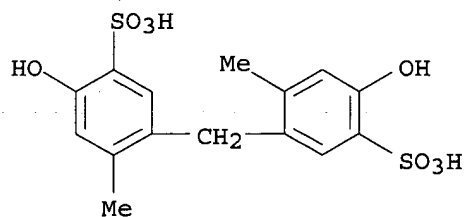
RN 79105-66-1 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl-, compd. with 1,4-diazabicyclo[2.2.2]octane (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 78480-14-5

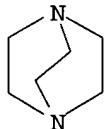
CMF C15 H16 O8 S2



CM 2

CRN 280-57-9

CMF C6 H12 N2

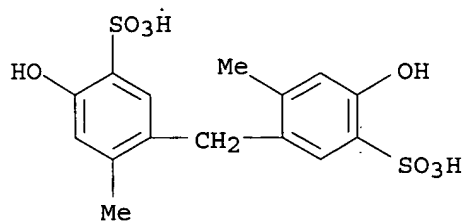


IT 78480-14-5P

RL: BAC (Biological activity or effector, except adverse); BSU (Biological study, unclassified); SPN (Synthetic preparation); BIOL (Biological study); PREP (Preparation)  
(prepn. of, as bactericide)

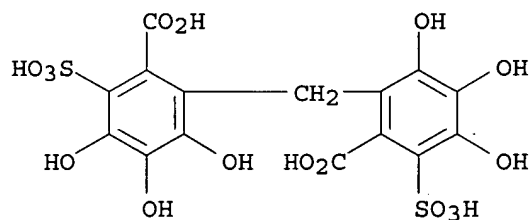
RN 78480-14-5 CAPLUS

CN Benzenesulfonic acid, 3,3'-methylenebis[6-hydroxy-4-methyl- (9CI) (CA INDEX NAME)

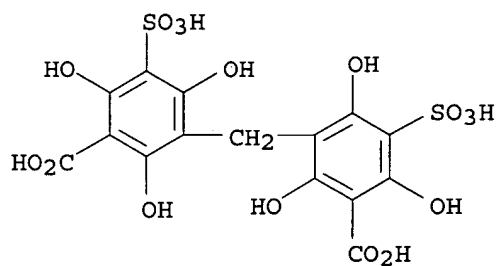


L7 ANSWER 40 OF 51 CAPLUS COPYRIGHT 2003 ACS  
 AN 1957:9584 CAPLUS  
 DN 51:9584  
 OREF 51:2043a-e  
 TI New and biologically active diphenylmethane derivatives  
 IN Hahn, Ladislaus A.; Fekete, Janos  
 PA Aktiebolaget "Ferrosan"  
 DT Patent  
 LA Unavailable  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2731494		19560117	US	
IT	102440-96-0, Gallic acid, 2,2'-methylenebis[6-sulfo-108012-19-7, Benzoic acid, 3,3'-methylenebis[2,4,6-trihydroxy-5-sulfo- (prepn. of)				
RN	102440-96-0	CAPLUS			
CN	Gallic acid, 2,2'-methylenebis[6-sulfo-	(6CI)		(CA INDEX NAME)	

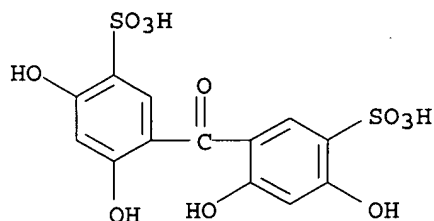


RN 108012-19-7 CAPLUS  
 CN Benzoic acid, 3,3'-methylenebis[2,4,6-trihydroxy-5-sulfo- (6CI) (CA INDEX NAME)

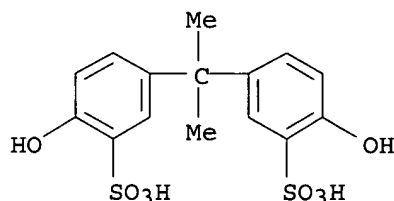




L7 ANSWER 41 OF 51 USPATFULL  
 AN 2002:230490 USPATFULL  
 TI Inhibition of pulp and paper yellowing using nitroxides,  
 hydroxylamines and other coadditives  
 IN Seltzer, Raymond R., New City, NY, United States  
 Wolf, Jean-Pierre, Courtaman, SWITZERLAND  
 Heitner, Cyril, Pierrefonds, CANADA  
 Schmidt, John A., L'ile Bizard, CANADA  
 McGarry, Peter F., L'ile Bizard, CANADA  
 Cunkle, Glen T., Stamford, CT, United States  
 Nelson, Randall B., Seattle, WA, United States  
 PA Ciba Specialty Chemicals Corporation, Tarrytown, NY, United States (U.S.  
 corporation)  
 PI US 6447644 B1 20020910  
 US 2002124980 A1 20020912  
 AI US 2001-974382 20011010 (9)  
 RLI Division of Ser. No. US 2000-573401, filed on 18 May 2000 Division of  
 Ser. No. US 1998-119567, filed on 20 Jul 1998, now patented, Pat. No. US  
 6254724, issued on 3 Jul 2001  
 PRAI US 1997-54968P 19970807 (60)  
 US 1997-53489P 19970723 (60)  
 DT Utility  
 FS GRANTED  
 EXNAM Primary Examiner: Griffin, Steven P.; Assistant Examiner: Halpern, Mark  
 LREP Stevenson, Tyler A., Hall, Luther A. R.  
 CLMN Number of Claims: 34  
 ECL Exemplary Claim: 1  
 DRWN 0 Drawing Figure(s); 0 Drawing Page(s)  
 LN.CNT 3054  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 184840-94-6  
 (inhibition of pulp and paper yellowing using nitroxides and other  
 co-additives)  
 RN 184840-94-6 USPATFULL  
 CN Benzenesulfonic acid, 3,3'-carbonylbis[4,6-dihydroxy-, disodium salt (9CI)  
 (CA INDEX NAME)



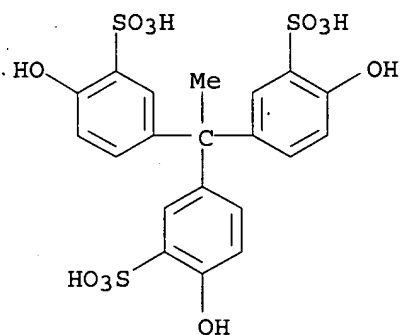
L7 ANSWER 44 OF 51 USPATFULL  
 AN 96:33735 USPATFULL  
 TI Ink compositions  
 IN Toan, Vien V., Lentigny, Switzerland  
 Laver, Hugh S., Reinach, Switzerland  
 Leppard, David G., Marly, Switzerland  
 PA Ciba-Geigy Corporation, Tarrytown, NY, United States (U.S. corporation)  
 PI US 5509957 19960423  
 AI US 1993-147706 19931104 (8)  
 PRAI CH 1992-3456 19921109  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Bell, Mark L.; Assistant Examiner: Hertzog, Scott L.  
 LREP Hall, Luther A. R., Kovaleski, Michele A.  
 CLMN Number of Claims: 11  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 619.  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 159411-67-3  
 (jet-printing inks, their stabilization and phenolsulfonic acids therefor)  
 RN 159411-67-3 USPATFULL  
 CN Benzenesulfonic acid, 3,3'-(1-methylethylidene)bis[6-hydroxy-, dilithium salt (9CI) (CA INDEX NAME)



●2 Li

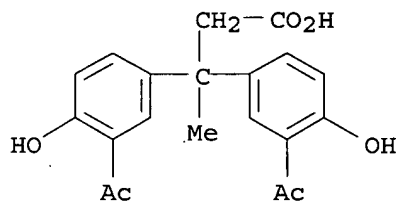
L7 ANSWER 45 OF 51 USPATFULL  
 AN 95:69368 USPATFULL  
 TI Functionalized tris(hydroxyphenyl) compounds  
 IN Fritsch, John R., Corpus Christi, TX, United States  
 Fruchey, Olan S., Corpus Christi, TX, United States  
 Kuila, Debasish, Corpus Christi, TX, United States  
 Kvakovszky, George, Corpus Christi, TX, United States  
 Murphy, Mark A., Corpus Christi, TX, United States  
 Sheehan, Michael T., Corpus Christi, TX, United States  
 Sounik, James R., Corpus Christi, TX, United States  
 Vicari, Richard, Corpus Christi, TX, United States  
 PA Hoechst Celanese Corp., Somerville, NJ, United States (U.S. corporation)  
 PI US 5438142 19950801  
 AI US 1993-105824 19930810 (8)  
 RLI Continuation-in-part of Ser. No. US 1992-921450, filed on 28 Jul 1992, now abandoned which is a continuation-in-part of Ser. No. US 1992-829123, filed on 3 Feb 1992, now abandoned  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Higel, Floyd D.  
 LREP Ferrell, Michael W.

CLMN Number of Claims: 2  
ECL Exemplary Claim: 1,2  
DRWN 2 Drawing Figure(s); 2 Drawing Page(s)  
LN.CNT 745  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
IT 170734-16-4, 1,1,1-Tris(3-sulfo-4-hydroxyphenyl)ethane  
(stain blocker for polymers)  
RN 170734-16-4 USPATFULL  
CN Benzenesulfonic acid, 3,3',3''-ethylidynetris[6-hydroxy- (9CI) (CA INDEX  
NAME)



=>

L7 ANSWER 47 OF 51 USPATFULL  
 AN 95:7868 USPATFULL  
 TI Thermosensitive recording material  
 IN Nishimura, Masaki, Tokyo, Japan  
 Toyofuku, Kunitaka, Sakura, Japan  
 PA New Oji Paper Co., Ltd., Tokyo, Japan (non-U.S. corporation)  
 PI US 5384303 19950124  
 AI US 1992-916693 19920722 (7)  
 PRAI JP 1991-251364 19910930  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Hess, B. Hamilton  
 LREP Armstrong, Westerman, Hattori, McLeland & Naughton  
 CLMN Number of Claims: 6  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 646  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 151533-18-5  
 (color-forming compns. contg. dye precursors and, for thermosensitive recording materials)  
 RN 151533-18-5 USPATFULL  
 CN Benzenepropanoic acid, 3-acetyl-.beta.-(3-acetyl-4-hydroxyphenyl)-4-hydroxy-.beta.-methyl-. (9CI) (CA INDEX NAME)



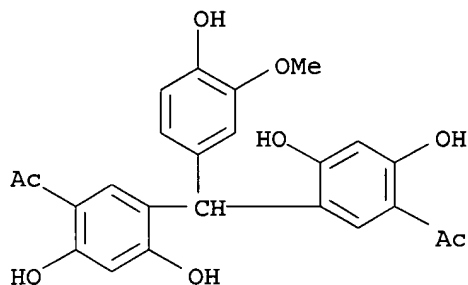
L7 ANSWER 48 OF 51 USPATFULL  
 AN 94:17899 USPATFULL  
 TI Positive type photoresist composition comprising polyaromatic **hydroxy** quinone diazide esters as the photosensitive ingredient  
 IN Uenishi, Kazuya, Shizuoka, Japan  
 Kawabe, Yasumasa, Shizuoka, Japan  
 Kokubo, Tadayoshi, Shizuoka, Japan  
 PA Fuji Photo Film Co., Ltd., Kanagawa, United States (non-U.S. corporation)  
 PI US 5290658 19940301  
 AI US 1992-873158 19920424 (7)  
 PRAI JP 1991-122851 19910426  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Schilling, Richard L.; Assistant Examiner: Chu, John S.  
 LREP Sughrue, Mion, Zinn, Macpeak & Seas  
 CLMN Number of Claims: 3  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 662  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 146837-32-3P  
 (prepn. and application of, in pos.-working high-resoln. heat-resistant novolak resin-contg. photoresists)  
 RN 146837-32-3 USPATFULL  
 CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with

1,1'-[[ (4-hydroxy-3-methoxyphenyl)methylene]bis (4,6-dihydroxy-3,1-phenylene)]bis[ethanone] (9CI) (CA INDEX NAME)

CM 1

CRN 146533-78-0

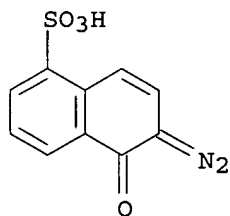
CMF C24 H22 O8



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



IT 135977-06-9P

(prepn. of)

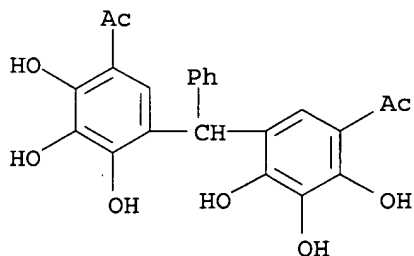
RN 135977-06-9 USPATFULL

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with  
1,1'-[(phenylmethylene)bis (4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone]  
(9CI) (CA INDEX NAME)

CM 1

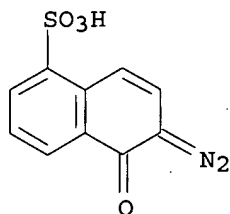
CRN 133682-16-3

CMF C23 H20 O8



CM 2

CRN 20546-03-6  
CMF C10 H6 N2 O4 S

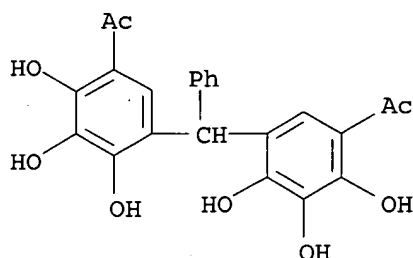


IT 133682-16-3

(reaction of, with naphthoquinonediazidosulfonyl chloride)

RN 133682-16-3 USPATFULL

CN Ethanone, 1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis-  
(9CI) (CA INDEX NAME)

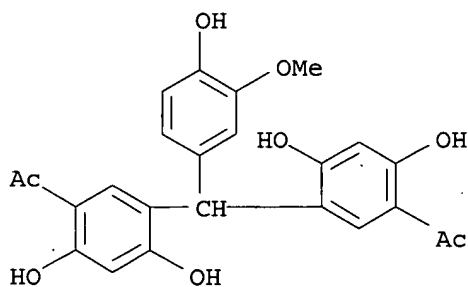


IT 146533-78-0

(reaction of, with naphthoquinonediazidosulfonyl chloride, in prepn. of  
photosensitive compd. for pos.-working photoresists based on novolak  
resin)

RN 146533-78-0 USPATFULL

CN Ethanone, 1,1'-[[[4-hydroxy-3-methoxyphenyl)methylene]bis(4,6-dihydroxy-  
3,1-phenylene)]bis- (9CI) (CA INDEX NAME)



L7 ANSWER 49 OF 51 USPATFULL

AN 92:104877 USPATFULL

TI Positive-working photoresist composition

IN Uenishi, Kazuya, Shizuoka, Japan

Sakaguchi, Shinji, Shizuoka, Japan

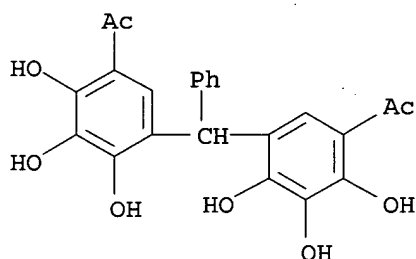
Kokubo, Tadayoshi, Shizuoka, Japan4)

PA Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S. corporation)

PI US 5173389 19921222

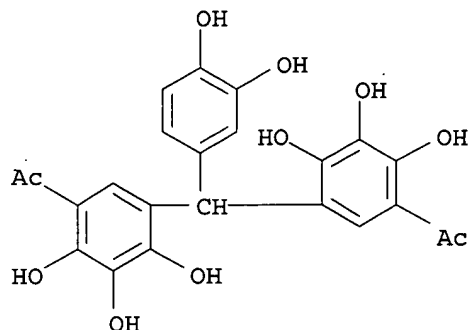
AI US 1990-514811 19900426 (7)

PRAI JP 1989-107013 19890426  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Bowers, Jr., Charles L.; Assistant Examiner: Chu, John S. Y.  
 LREP Sughrue, Mion, Zinn, Macpeak & Seas  
 CLMN Number of Claims: 13  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 760  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 133682-16-3D, dimethylhydroxybenzyl deriv., diazidonaphthoquinone sulfate  
 (pos. photoresists contg. alkali-sol. novolak resins and)  
 RN 133682-16-3 USPATFULL  
 CN Ethanone, 1,1'-[(phenylmethylene)bis(4,5,6-trihydroxy-3,1-phenylene)]bis-(9CI) (CA INDEX NAME)



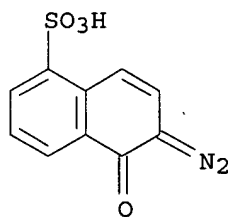
L7 ANSWER 50 OF 51 USPATFULL  
 AN 92:82677 USPATFULL  
 TI Positive type photoresist composition comprising as a photosensitive ingredient a derivative of a triphenylmethane condensed with an o-quinone diazide  
 IN Uenishi, Kazuya, Shizuoka, Japan  
 Kawabe, Yasumasa, Shizuoka, Japan  
 Kokubo, Tadayoshi, Shizuoka, Japan  
 PA Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S. corporation)  
 PI US 5153096 19921006  
 AI US 1991-670513 19910318 (7)  
 RLI Continuation of Ser. No. US 1989-301763, filed on 26 Jan 1989, now abandoned  
 PRAI JP 1988-14898 19880126  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Schilling, Richard L.; Assistant Examiner: Chu, John S.  
 LREP Sughrue, Mion, Zinn Macpeak & Seas  
 CLMN Number of Claims: 6  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 602  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 126776-67-8  
 (sulfonylation of, in prepn. of pos.-working photoresist)  
 RN 126776-67-8 USPATFULL  
 CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, ester with 1,1'-[[[(3,4-dihydroxyphenyl)methylene]bis(4,5,6-trihydroxy-3,1-phenylene)]bis(ethanone)] (9CI) (CA INDEX NAME)

CRN 143868-74-0  
CMF C23 H20 O10



CM 2

CRN 20546-03-6  
CMF C10 H6 N2 O4 S



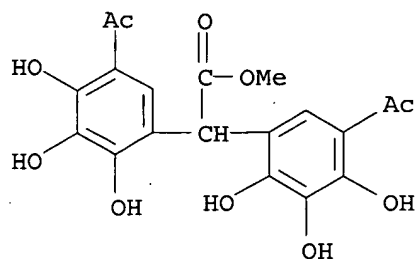
L7 ANSWER 51 OF 51 USPATFULL  
AN 92:12832 USPATFULL  
TI Positive photoresist composition utilizing O-quinonediazide and novolak resin  
IN Uenishi, Kazuya, Shizuoka, Japan  
Kawabe, Yasumasa, Shizuoka, Japan  
Kokubo, Tadayoshi, Shizuoka, Japan  
PA Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S. corporation)  
PI US 5089373 19920218  
AI US 1989-363568 19890607 (7)  
PRAI JP 1988-139904 19880607  
DT Utility  
FS Granted  
EXNAM Primary Examiner: Bowers, Jr., Charles L.; Assistant Examiner: Young, Christopher G.  
LREP Sughrue, Mion, Zinn, Macpeak & Seas  
CLMN Number of Claims: 9  
ECL Exemplary Claim: 1  
DRWN No Drawings  
LN.CNT 609  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
IT 128152-08-9 128152-12-5 128197-52-4  
(pos.-working photoresist compn. contg.)  
RN 128152-08-9 USPATFULL  
CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-2,3,4-trihydroxy-, methyl ester, 6-diazo-5,6-dihydro-5-oxo-1-naphthalenesulfonate (9CI) (CA INDEX NAME)



CM 1

CRN 128347-37-5

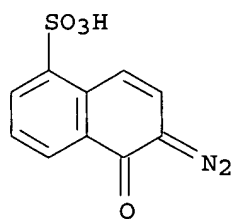
CMF C19 H18 O10



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



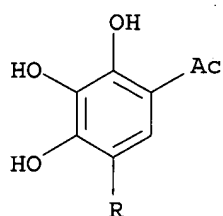
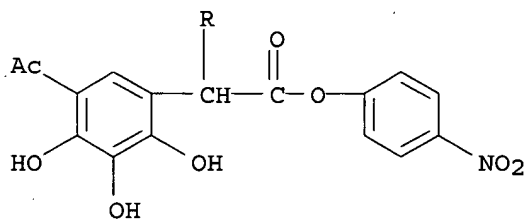
RN 128152-12-5 USPATFULL

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-2,3,4-trihydroxy-, 4-nitrophenyl ester, 6-diazo-5,6-dihydro-5-oxo-1-naphthalenesulfonate (9CI) (CA INDEX NAME)

CM 1

CRN 128347-40-0

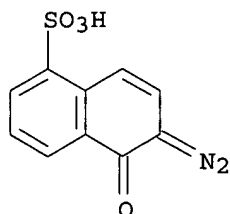
CMF C24 H19 N O12



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



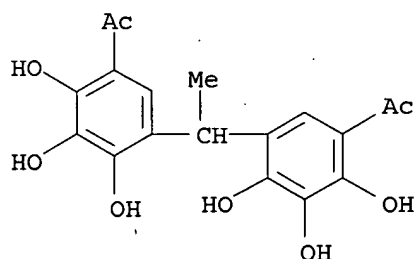
RN 128197-52-4 USPATFULL

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, tetraester with  
1,1'-[ethyldienebis(4,5,6-trihydroxy-3,1-phenylene)]bis[ethanone] (9CI)  
(CA INDEX NAME)

CM 1

CRN 128197-51-3

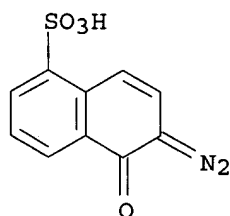
CMF C18 H18 O8



CM 2

CRN 20546-03-6

CMF C10 H6 N2 O4 S



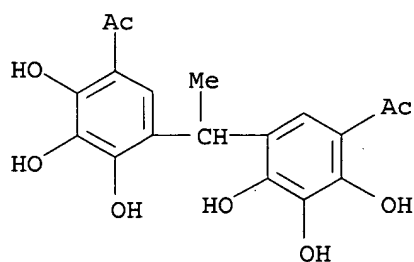
IT 128197-51-3, 1,1-(5,5'-Diacetyl-2,3,4,2',3',4'-  
hexahydroxy)diphenylethane 128347-37-5, 1,1-(5,3'-Diacetyl-  
2,3,4,4',5',6'-hexahydroxy)diphenylacetic acid methyl ester  
128347-40-0

(reaction of, in prepn. of naphthoquinonediazide ester for pos.-working  
photoresist compn.)

RN 128197-51-3 USPATFULL

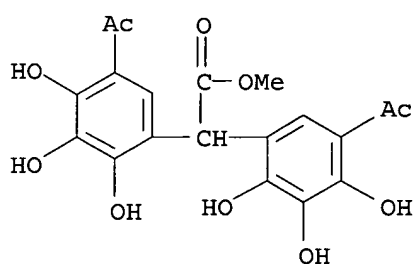
CN Ethanone, 1,1'-[ethyldienebis(4,5,6-trihydroxy-3,1-phenylene)]bis- (9CI)

(CA INDEX NAME)



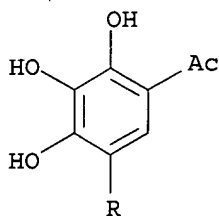
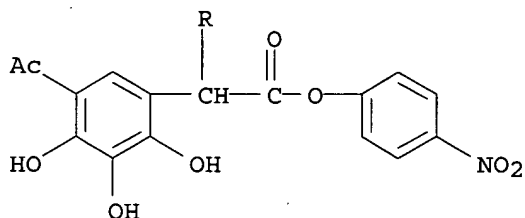
RN 128347-37-5 USPATFULL

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-2,3,4-trihydroxy-, methyl ester (9CI) (CA INDEX NAME)



RN 128347-40-0 USPATFULL

CN Benzeneacetic acid, 5-acetyl-.alpha.-(5-acetyl-2,3,4-trihydroxyphenyl)-2,3,4-trihydroxy-, 4-nitrophenyl ester (9CI) (CA INDEX NAME)



=>

(FILE 'HOME' ENTERED AT 10:36:08 ON 08 JUL 2003)

FILE 'REGISTRY' ENTERED AT 10:36:19 ON 08 JUL 2003

L1           STRUCTURE UPLOADED  
L2           0 S L1  
L3           103 S L1 FUL  
L4           0 S L3 AND CLATHRATE

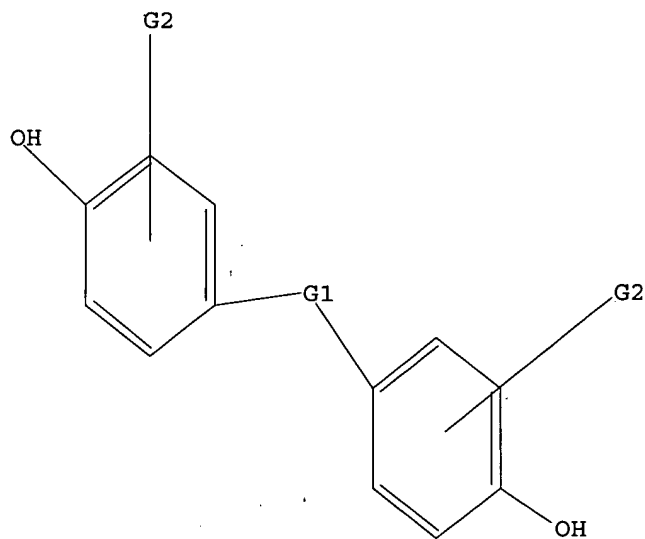
FILE 'CAPLUS, USPATFULL' ENTERED AT 10:38:43 ON 08 JUL 2003

L5           78 S L3  
L6           0 S L5 AND CLATHRATE  
L7           51 S L5 AND ?HYDROXY?

=> d l1

L1 HAS NO ANSWERS

L1           STR



G1 C,O,S,N

G2 SO2,C(O)CH3

Structure attributes must be viewed using STN Express query preparation.